CAS ONLINE PRINTOUT

=> D HIS

(FILE 'HOME' ENTERED AT 07:33:52 ON 12 MAR 2007)

FILE 'REGISTRY' ENTERED AT 07:33:57 ON 12 MAR 2007

FILE 'CAPLUS' ENTERED AT 07:34:03 ON 12 MAR 2007
E US20060208227/PN
L1 1 S E3
SELECT RN L1 1

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L2 20 S E1-E20
L3 1021 S C21 H30 N2 O2/MF
L4 1 S L3 AND L2

FILE 'REGISTRY' ENTERED AT 07:42:37 ON 12 MAR 2007
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L6 4 S L5
L7 1 S L5 CSS
L8 111 S L5 CSS FUL
L9 STRUCTURE UPLOADED
L10 STRUCTURE UPLOADED
L11 4 SEARCH L10 CSS SUB=L8 FUL

FILE 'CAPLUS' ENTERED AT 07:48:26 ON 12 MAR 2007
L12 2 S L11

=> D L10
L10 HAS NO ANSWERS
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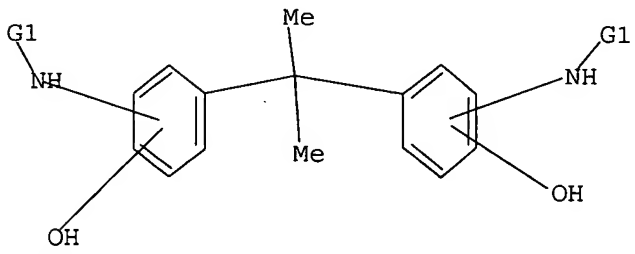


G1 Me,Et,n-Pr,i-Pr,n-Bu,i-Bu,s-Bu,t-Bu

Structure attributes must be viewed using STN Express query preparation.

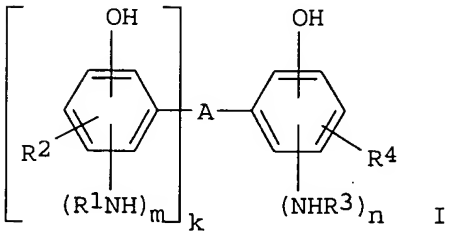
=> D BIB ABS HITSTR 1-2

L12 ANSWER 1 OF 2 CAPLUS COPYRIGHT 2007 ACS on STN
AN 2006:1247858 CAPLUS
DN 146:28395
TI Aminophenol curing agents for polyurethanes for reaction injection molding
IN Yasuyoshi, Matsunori; Fujioka, Toyozo; Shiraki, Yasushi
PA Idemitsu Kosan Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 18pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

CAS ONLINE PRINTOUT

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2006321834	A	20061130	JP 2005-143805	20050517
PRAI	JP 2005-143805		20050517		

GI



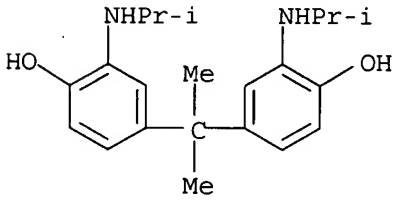
I

AB The curing agents comprise aminophenols represented by the general formula I [R1-R4 = H, C1-20 alkyl; A = direct bond, O, NH, SO2, CH2, CMe2; the OH and NH2 on one benzene ring exist adjacent to each other; k = 0, 1; m, n = 1, 2]. The curing agents are halogen-free, thereby being non-hazardous, and are capable of changing curing speed as desired. Thus, 150 g bisphenol A in MEK was treated with HNO3 to give 2,2-bis(3-nitro-4-hydroxyphenyl)propane, 200 g of which was reduced with H in DMF to give 2,2-bis(3-amino-4-hydroxyphenyl)propane (II) in yield 73%. A liquid hardener masterbatch containing 20% II in methoxy-N,N'-dimethylpropionamide was mixed with an isocyanate-modified urethane prepolymer (MC 50) at rate NCO/active H = 1.0, cast in a mold, pressed at 150°, and aged at 120° for 1 h to give a sheet showing tensile strength 0.88, 100% modulus 1.101 MPa, elongation 110%, JIS A Durometer hardness 46, and pot life 1 min.

IT 776993-17-0P 776993-18-1P
RL: IMF (Industrial manufacture); MOA (Modifier or additive use); PREP (Preparation); USES (Uses)
(aminophenol curing agents for polyurethanes for reaction injection molding)

RN 776993-17-0 CAPLUS

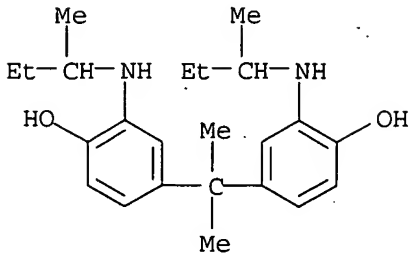
CN Phenol, 4,4'-(1-methylethylidene)bis[2-[(1-methylethyl)amino]- (9CI) (CA INDEX NAME)



RN 776993-18-1 CAPLUS

CN Phenol, 4,4'-(1-methylethylidene)bis[2-[(1-methylpropyl)amino]- (9CI) (CA INDEX NAME)

CAS ONLINE PRINTOUT



IT 915956-48-8P 915956-50-2P
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(crosslinked; aminophenol curing agents for polyurethanes for reaction injection molding)

RN 915956-48-8 CAPLUS

CN Phenol, 4,4'-(1-methylethylidene)bis[2-[(1-methylethyl)amino]-, polymer with MC 50 (polyurethane) (CA INDEX NAME)

CM 1

CRN 915956-15-9
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

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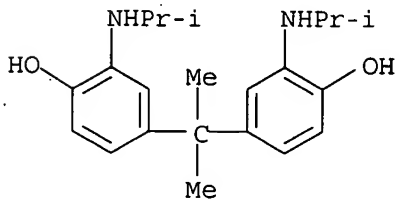
CRN 776993-17-0
CMF C21 H30 N2 O2



RN 915956-50-2 CAPLUS

CN Phenol, 4,4'-(1-methylethylidene)bis[2-[(1-methylpropyl)amino]-, polymer with MC 50 (polyurethane) (CA INDEX NAME)

CM 1

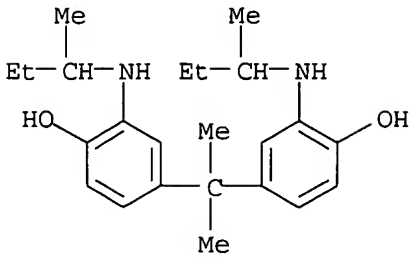
CRN 915956-15-9
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 2

CRN 776993-18-1
CMF C23 H34 N2 O2

CAS ONLINE PRINTOUT

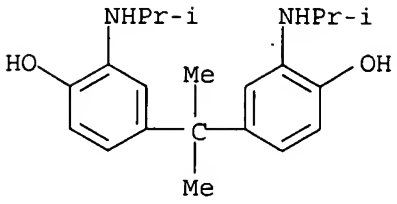


L12 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2007 ACS on STN
AN 2004:872832 CAPLUS
DN 141:350875
TI Aromatic hydroxyamine derivatives for antioxidants in plastics, rubbers, and petroleum products
IN Shiraki, Yasushi
PA Idemitsu Petrochemical Co. Ltd., Japan
SO PCT Int. Appl., 34 pp.
CODEN: PIXXD2
DT Patent
LA Japanese
FAN.CNT 1

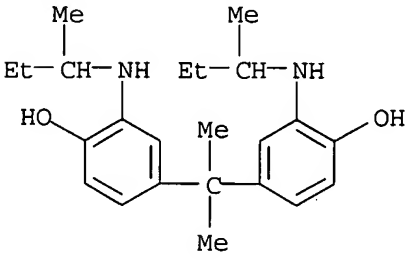
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 2004090070	A1	20041021	WO 2004-JP4608	20040331
	W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW				
	RW: BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
	EP 1612254	A1	20060104	EP 2004-724787	20040331
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK				
	US 2006208227	A1	20060921	US 2005-551451	20050929
PRAI	JP 2003-99104	A	20030402		
	JP 2003-410630	A	20031209		
	WO 2004-JP4608	W	20040331		

OS MARPAT 141:350875
AB The derivs. are represented by (C6HXYR2A)nC6H(OH)(NHR1)R3, wherein R1-R3 = H or alkyl groups, X = H or OH, Y = H or NHR1, A = direct bond, O, NH, SO2, CH2 or C(CH3)2; and OH and NHR1 are next to each other when introduced into a single benzene ring, n = 0 or 1, but R1 ≠ H when n = 0. Stirring o-aminophenol 12, 2-iodopropane 22.4, and KHCO3 11.4 g in 60 mL DMF for 5 h gave a 98.4%-pure 2-(isopropylamino)phenol that started to absorb O after 370 min in an antioxidn. test.
IT 776993-17-0P
RL: IMF (Industrial manufacture); MOA (Modifier or additive use); PREP (Preparation); USES (Uses)
(aromatic hydroxyamine derivs. for antioxidants in plastics, rubbers, and petroleum products)
RN 776993-17-0 CAPLUS
CN Phenol, 4,4'-(1-methylethylidene)bis[2-[(1-methylethyl)amino]- (9CI) (CA INDEX NAME)

CAS ONLINE PRINTOUT



IT 776993-18-1
RL: MOA (Modifier or additive use); RCT (Reactant); RACT (Reactant or reagent); USES (Uses)
(aromatic hydroxyamine derivs. for antioxidants in plastics, rubbers, and petroleum products)
RN 776993-18-1 CAPLUS
CN Phenol, 4,4'-(1-methylethylidene)bis[2-[(1-methylpropyl)amino]- (9CI) (CA INDEX NAME)



RE.CNT 9 THERE ARE 9 CITED REFERENCES AVAILABLE FOR THIS RECORD
ALL CITATIONS AVAILABLE IN THE RE FORMAT

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CAS ONLINE PRINTOUT

> D HIS

(FILE 'HOME' ENTERED AT 07:33:52 ON 12 MAR 2007)

FILE 'REGISTRY' ENTERED AT 07:33:57 ON 12 MAR 2007

FILE 'CAPLUS' ENTERED AT 07:34:03 ON 12 MAR 2007
E US20060208227/PN
L1 1 S E3
SELECT RN L1 1

FILE 'REGISTRY' ENTERED AT 07:34:30 ON 12 MAR 2007
L2 20 S E1-E20
L3 1021 S C21 H30 N2 O2/MF
L4 1 S L3 AND L2

FILE 'REGISTRY' ENTERED AT 07:42:37 ON 12 MAR 2007
L5 STRUCTURE UPLOADED
L6 4 S L5
L7 1 S L5 CSS
L8 111 S L5 CSS FUL
L9 STRUCTURE UPLOADED
L10 STRUCTURE UPLOADED
L11 4 SEARCH L10 CSS SUB=L8 FUL

FILE 'CAPLUS' ENTERED AT 07:48:26 ON 12 MAR 2007
L12 2 S L11

FILE 'REGISTRY' ENTERED AT 07:51:55 ON 12 MAR 2007
L13 STRUCTURE UPLOADED
L14 2 S L13 FUL
L15 0 S L13 CSS
L16 STRUCTURE UPLOADED
L17 0 S L16 CSS
L18 SCREEN 1929 OR 2026 OR 2021 OR 2016 OR 2006 OR 1840
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L20 QUE L19 NOT L18
L21 0 S L20 CSS
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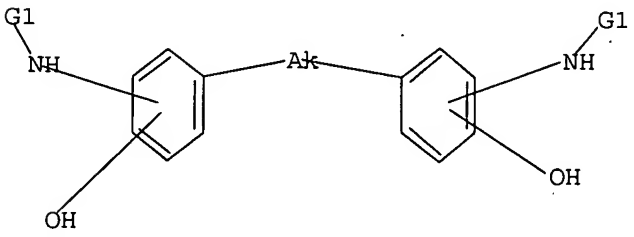
L23 2 S L22

=> D L19
L19 HAS NO ANSWERS
L19 STR



G1 n-Pr,i-Pr,n-Bu,i-Bu,s-Bu,t-Bu

Structure attributes must be viewed using STN Express query preparation.

CAS ONLINE PRINTOUT

=> D BIB ABS HITSTR 1-2

L23 ANSWER 1 OF 2 CAPLUS COPYRIGHT 2007 ACS on STN
AN 2006:1247858 CAPLUS
DN 146:28395
TI Aminophenol curing agents for polyurethanes for reaction injection molding
IN Yasuyoshi, Matsunori; Fujioka, Toyozo; Shiraki, Yasushi
PA Idemitsu Kosan Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 18pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2006321834	A	20061130	JP 2005-143805	20050517
PRAI	JP 2005-143805		20050517		

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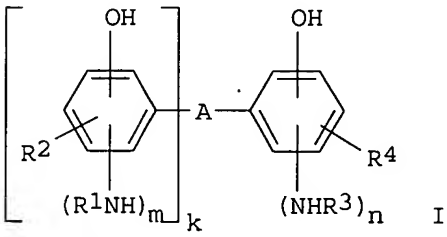
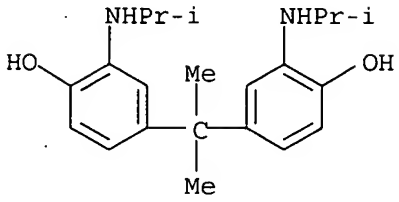


I

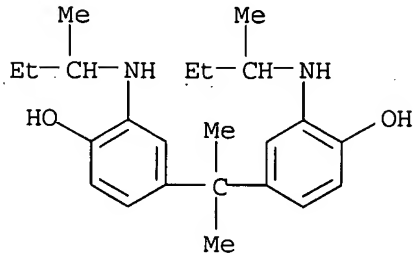
AB The curing agents comprise aminophenols represented by the general formula I [R1-R4 = H, C1-20 alkyl; A = direct bond, O, NH, SO2, CH2, CMe2; the OH and NH2 on one benzene ring exist adjacent to each other; k = 0, 1; m, n = 1, 2]. The curing agents are halogen-free, thereby being non-hazardous, and are capable of changing curing speed as desired. Thus, 150 g bisphenol A in MEK was treated with HNO3 to give 2,2-bis(3-nitro-4-hydroxyphenyl)propane, 200 g of which was reduced with H in DMF to give 2,2-bis(3-amino-4-hydroxyphenyl)propane (II) in yield 73%. A liquid hardener masterbatch containing 20% II in methoxy-N,N'-dimethylpropionamide was mixed with an isocyanate-modified urethane prepolymer (MC 50) at rate NCO/active H = 1.0, cast in a mold, pressed at 150°, and aged at 120° for 1 h to give a sheet showing tensile strength 0.88, 100% modulus 1.101 MPa, elongation 110%, JIS A Durometer hardness 46, and pot life 1 min.

IT 776993-17-0P 776993-18-1P
RL: IMF (Industrial manufacture); MOA (Modifier or additive use); PREP (Preparation); USES (Uses)
(aminophenol curing agents for polyurethanes for reaction injection molding)

RN 776993-17-0 CAPLUS
CN Phenol, 4,4'-(1-methylethylidene)bis[2-[(1-methylethyl)amino]- (9CI) (CA INDEX NAME)



RN 776993-18-1 CAPLUS
CN Phenol, 4,4'-(1-methylethylidene)bis[2-[(1-methylpropyl)amino]- (9CI) (CA INDEX NAME)



IT 915956-48-8P 915956-50-2P
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(crosslinked; aminophenol curing agents for polyurethanes for reaction injection molding)
RN 915956-48-8 CAPLUS
CN Phenol, 4,4'-(1-methylethylidene)bis[2-[(1-methylethyl)amino]-, polymer with MC 50 (polyurethane) (CA INDEX NAME)

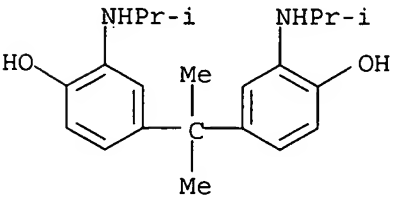
CM 1

CRN 915956-15-9
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 2

CRN 776993-17-0
CMF C21 H30 N2 O2



RN 915956-50-2 CAPLUS
CN Phenol, 4,4'-(1-methylethylidene)bis[2-[(1-methylpropyl)amino]-, polymer with MC 50 (polyurethane) (CA INDEX NAME)

CAS ONLINE PRINTOUT

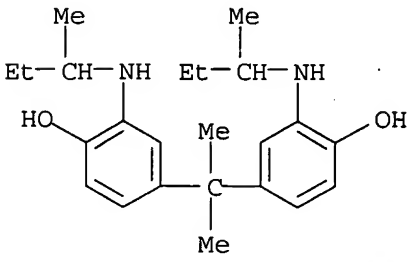
CM 1

CRN 915956-15-9
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 2

CRN 776993-18-1
CMF C23 H34 N2 O2



L23 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2007 ACS on STN
AN 2004:872832 CAPLUS
DN 141:350875
TI Aromatic hydroxyamine derivatives for antioxidants in plastics, rubbers, and petroleum products
IN Shiraki, Yasushi
PA Idemitsu Petrochemical Co. Ltd., Japan
SO PCT Int. Appl., 34 pp.
CODEN: PIXXD2
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 2004090070	A1	20041021	WO 2004-JP4608	20040331
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	RW: BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
	EP 1612254	A1	20060104	EP 2004-724787	20040331
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK				
	US 2006208227	A1	20060921	US 2005-551451	20050929
PRAI	JP 2003-99104	A	20030402		
	JP 2003-410630	A	20031209		
	WO 2004-JP4608	W	20040331		

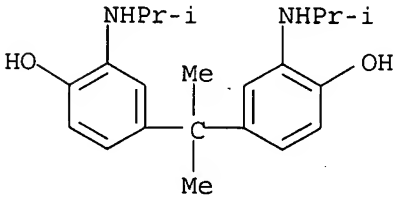
OS MARPAT 141:350875
AB The derivs. are represented by (C6HXYR2A)nC6H(OH)(NHR1)R3, wherein R1-R3 =

H or alkyl groups, X = H or OH, Y = H or NHR1, A = direct bond, O, NH, SO2, CH2 or C(CH3)2; and OH and NHR1 are next to each other when introduced into a single benzene ring, n = 0 or 1, but R1 ≠ H when n = 0. Stirring o-aminophenol 12, 2-iodopropane 22.4, and KHCO3 11.4 g in 60 mL DMF for 5 h gave a 98.4%-pure 2-(isopropylamino)phenol that started to absorb O after 370 min in an antioxidn. test.

IT 776993-17-0P
RL: IMF (Industrial manufacture); MOA (Modifier or additive use); PREP (Preparation); USES (Uses)
(aromatic hydroxyamine derivs. for antioxidants in plastics, rubbers, and petroleum products)

RN 776993-17-0 CAPLUS

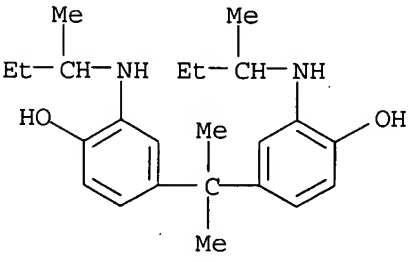
CN Phenol, 4,4'-(1-methylethylidene)bis[2-[(1-methylethyl)amino]- (9CI) (CA INDEX NAME)



IT 776993-18-1
RL: MOA (Modifier or additive use); RCT (Reactant); RACT (Reactant or reagent); USES (Uses)
(aromatic hydroxyamine derivs. for antioxidants in plastics, rubbers, and petroleum products)

RN 776993-18-1 CAPLUS

CN Phenol, 4,4'-(1-methylethylidene)bis[2-[(1-methylpropyl)amino]- (9CI) (CA INDEX NAME)



RE.CNT 9 THERE ARE 9 CITED REFERENCES AVAILABLE FOR THIS RECORD
ALL CITATIONS AVAILABLE IN THE RE FORMAT

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     FILE 'REGISTRY' ENTERED AT 07:33:57 ON 12 MAR 2007

     FILE 'CAPLUS' ENTERED AT 07:34:03 ON 12 MAR 2007
                E US20060208227/PN
L1            1 S E3
                SELECT RN L1 1

     FILE 'REGISTRY' ENTERED AT 07:34:30 ON 12 MAR 2007
L2           20 S E1-E20
L3         1021 S  C21 H30 N2 O2/MF
L4            1 S L3 AND L2

     FILE 'REGISTRY' ENTERED AT 07:42:37 ON 12 MAR 2007
L5                STRUCTURE UPLOADED
L6            4 S L5
L7            1 S L5 CSS
L8          111 S L5 CSS FUL
L9                STRUCTURE UPLOADED
L10               STRUCTURE UPLOADED
L11           4 SEARCH L10 CSS  SUB=L8 FUL

     FILE 'CAPLUS' ENTERED AT 07:48:26 ON 12 MAR 2007
L12           2 S L11

     FILE 'REGISTRY' ENTERED AT 07:51:55 ON 12 MAR 2007
L13               STRUCTURE UPLOADED
L14           2 S L13 FUL
L15           0 S L13 CSS
L16               STRUCTURE UPLOADED
L17           0 S L16 CSS
L18               SCREEN 1929 OR  2026 OR  2021 OR  2016 OR  2006 OR  1840
L19               STRUCTURE UPLOADED
L20               QUE L19 NOT L18
L21           0 S L20 CSS
L22           4 S L20 CSS FUL

     FILE 'CAPLUS' ENTERED AT 07:58:56 ON 12 MAR 2007
L23           2 S L22

     FILE 'CAPLUS' ENTERED AT 08:00:19 ON 12 MAR 2007

     FILE 'USPATFULL' ENTERED AT 08:00:28 ON 12 MAR 2007
L24          24 S L8
L25           0 S ANTIOXIIDANT
L26       58827 S ANTIOXIDANT
L27           6 S L26 AND L24

=> D BIB ABS HITSTR 14-24 L24

L24  ANSWER 14 OF 24  USPATFULL on STN
AN     2002:17315  USPATFULL
TI     Mitochondria protecting agents for treating mitochondria associated
       diseases
IN     Ghosh, Soumitra S., San Diego, CA, UNITED STATES
       Miller, Scott W., San Marcos, CA, UNITED STATES
       Davis, Robert E., San Diego, CA, UNITED STATES
       Moos, Walter H., Oakland, CA, UNITED STATES
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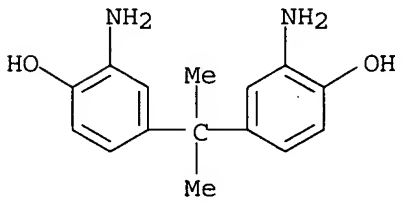
CAS ONLINE PRINTOUT

PI US 2002010195 A1 20020124
US 6498191 B2 20021224
AI US 2000-733271 A1 20001207 (9)
RLI Continuation of Ser. No. US 1999-237999, filed on 26 Jan 1999, ABANDONED
PRAI US 1998-72484P 19980126 (60)
US 1998-72487P 19980126 (60)
US 1998-72483P 19980126 (60)
US 1998-72482P 19980126 (60)
DT Utility
FS APPLICATION
LREP SEED INTELLECTUAL PROPERTY LAW GROUP PLLC, 701 FIFTH AVE, SUITE 6300, SEATTLE, WA, 98104-7092
CLMN Number of Claims: 35
ECL Exemplary Claim: 1
DRWN No Drawings
LN.CNT 1688
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
AB The present invention relates generally to mitochondria protecting agents for treating diseases in which mitochondrial dysfunction leads to tissue degeneration and, more specifically, to compounds, compositions and methods related to the same. The methods of this invention involve administration of a pharmaceutically effective amount of a mitochondria protecting agent to a warm-blooded animal in need thereof, and composition of this invention contain a mitochondria protecting agent in combination with a pharmaceutically acceptable carrier or diluent. Mitochondrial associated diseases which may be treated by the present invention include (but are not limited to) Alzheimer's Disease, diabetes mellitus, Parkinson's Disease, neuronal and cardiac ischemia, Huntington's disease and stroke.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT 1220-78-6P
(preparation of mitochondria protecting agents)
RN 1220-78-6 USPATFULL
CN Phenol, 4,4'-(1-methylethylidene)bis[2-amino- (CA INDEX NAME)



L24 ANSWER 15 OF 24 USPATFULL on STN
AN 2001:56077 USPATFULL
TI Polymaleimide and polyimide photo-alignment materials for LC display
IN Choi, Hwan Jae, Taejeon, Korea, Republic of
Kim, Joo-Young, Taejeon, Korea, Republic of
PA Cheil Industries Inc., Korea, Republic of (non-U.S. corporation)
Samsung Electronics Co., Ltd., Korea, Republic of (non-U.S. corporation)
PI US 6218501 B1 20010417
AI US 1999-353930 19990715 (9)
PRAI KR 1998-28532 19980715
DT Utility
FS Granted
EXNAM Primary Examiner: Hampton-Hightower, P.
LREP Woodcock Washburn Kurtz Mackiewicz & Norris

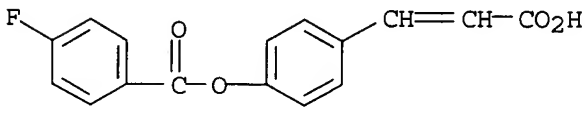
CAS ONLINE PRINTOUT

CLMN Number of Claims: 5
ECL Exemplary Claim: 1
DRWN 2 Drawing Figure(s); 2 Drawing Page(s)
LN.CNT 505
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
AB The present invention relates to a cinnamatic photo-polymerization type homopolymeric or copolymeric alignment material, in which polymaleimide is singly used as the main chain, or is combined with styrene, hydroxystyrene or acrylonitrile to form a copolymer so as to be used as the main chain, or polyimide is used as the main chain.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT 259096-65-6P, 2,2-Bis(3-amino-4-hydroxyphenyl)propane-4-(2,5-dioxotetrahydrofuran-3-yl)-tetralin-1,2-dicarboxylic anhydride copolymer p-(p-fluorobenzoyloxy)cinnamate 259096-66-7P, 2,2-Bis(3-amino-4-hydroxyphenyl)propane-meso-butane-1,2,3,4-tetracarboxylic dianhydride copolymer p-(p-fluorobenzoyloxy)cinnamate (photopolymerizable polymaleimides and polyimides bearing cinnamate groups for optical orientation materials for liquid crystal displays, and their manufacture of the materials by non-rubbing process)
RN 259096-65-6 USPATFULL
CN Naphtho[1,2-c]furan-1,3-dione, 3a,4,5,9b-tetrahydro-5-(tetrahydro-2,5-dioxo-3-furanyl)-, polymer with 4,4'-(1-methylethylidene)bis[2-aminophenol], 3-[4-[(4-fluorobenzoyl)oxy]phenyl]-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 259093-69-1
CMF C16 H11 F O4

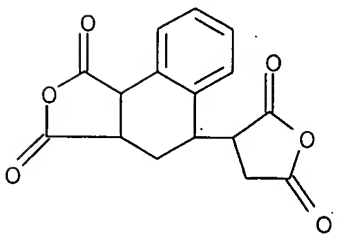


CM 2

CRN 259093-72-6
CMF (C16 H12 O6 . C15 H18 N2 O2)x
CCI PMS

CM 3

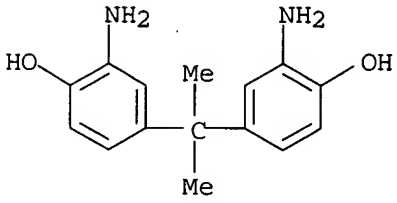
CRN 13912-65-7
CMF C16 H12 O6



CAS ONLINE PRINTOUT

CM 4

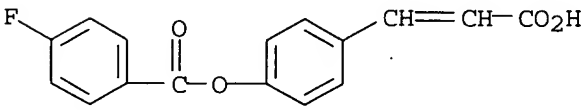
CRN 1220-78-6
CMF C15 H18 N2 O2



RN 259096-66-7 USPATFULL
CN Cyclobuta[1,2-c:3,4-c']difurantetrone, tetrahydro-, polymer with 4,4'-(1-methylethylidene)bis[2-aminophenol], 3-[4-[(4-fluorobenzoyl)oxy]phenyl]-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 259093-69-1
CMF C16 H11 F O4

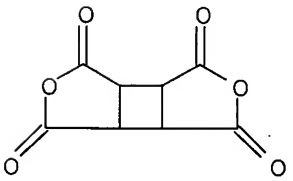


CM 2

CRN 259093-74-8
CMF (C15 H18 N2 O2 . C8 H4 O6)x
CCI PMS

CM 3

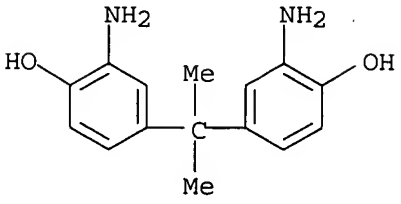
CRN 4415-87-6
CMF C8 H4 O6



CM 4

CRN 1220-78-6
CMF C15 H18 N2 O2

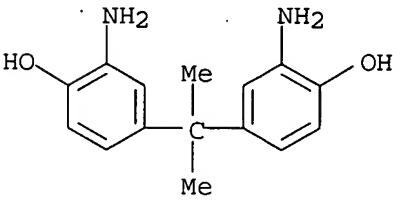
CAS ONLINE PRINTOUT



IT 1220-78-6P, 2,2-Bis(3-amino-4-hydroxyphenyl)propane
259093-72-6P, 2,2-Bis(3-amino-4-hydroxyphenyl)propane-4-(2,5-dioxotetrahydrofuran-3-yl)-tetralin-1,2-dicarboxylic anhydride copolymer
259093-74-8P, 2,2-Bis(3-amino-4-hydroxyphenyl)propane-meso-butane-1,2,3,4-tetracarboxylic dianhydride copolymer
(photopolymerizable polymaleimides and polyimides bearing cinnamate groups for optical orientation materials for liquid crystal displays, and their manufacture of the materials by non-rubbing process)

RN 1220-78-6 USPATFULL

CN Phenol, 4,4'-(1-methylethylidene)bis[2-amino- (CA INDEX NAME)

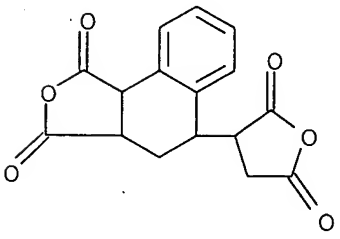


RN 259093-72-6 USPATFULL

CN Naphtho[1,2-c]furan-1,3-dione, 3a,4,5,9b-tetrahydro-5-(tetrahydro-2,5-dioxo-3-furanyl)-, polymer with 4,4'-(1-methylethylidene)bis[2-aminophenol] (9CI) (CA INDEX NAME)

CM 1

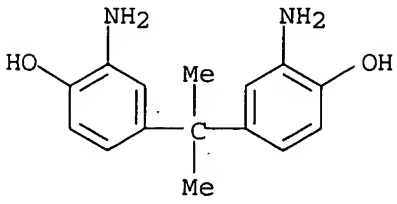
CRN 13912-65-7
CMF C16 H12 O6



CM 2

CRN 1220-78-6
CMF C15 H18 N2 O2

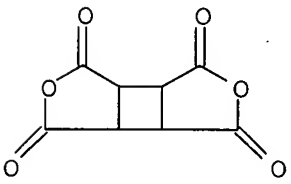
CAS ONLINE PRINTOUT



RN 259093-74-8 USPATFULL
CN Cyclobuta[1,2-c:3,4-c']difurantetrone, tetrahydro-, polymer with 4,4'-(1-methylethylidene)bis[2-aminophenol] (9CI) (CA INDEX NAME)

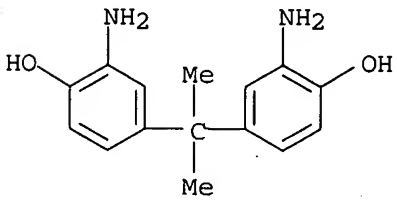
CM 1

CRN 4415-87-6
CMF C8 H4 O6



CM 2

CRN 1220-78-6
CMF C15 H18 N2 O2



L24 ANSWER 16 OF 24 USPATFULL on STN
AN 2001:40570 USPATFULL
TI Polybenzoxazole resin and precursor thereof
IN Saito, Hidenori, Yokohama, Japan
Nakajima, Michio, Kawasaki, Japan
Watanabe, Tsuyoshi, Boston, MA, United States
Tokuhiro, Maki, Kawasaki, Japan
PA Sumitomo Bakelite Company Limited, Tokyo, Japan (non-U.S. corporation)
PI US 6204356 B1 20010320
AI US 1999-404156 19990927 (9)
PRAI JP 1998-275185 19980929
DT Utility
FS Granted
EXNAM Primary Examiner: Hampton-Hightower, P.
LREP Smith, Gambrell & Russell, LLP
CLMN Number of Claims: 2
ECL Exemplary Claim: 1

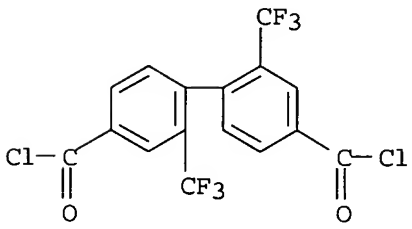
CAS ONLINE PRINTOUT

DRWN No Drawings
LN.CNT 303
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
AB Heat resistant polybenzoxazole resins useful as layer insulation films and protective films for semiconductor, layer insulation films for multilayer circuits, cover coats for flexible copper-clad sheets, solder resist films, liquid crystal-aligned films and the like. These resins have excellent thermal, electrical, physical and mechanical characteristics. Polybenzoxazole precursors are provided, represented by the general formula (A), and are used to obtain polybenzoxazole resins, represented by the general formula (D). In the formulas (A) and (D), n denotes an integer from 2-1000, and X denotes a structure having a formula selected from structures indicated at (B). In the formulas at (B), Y denotes a structure having a formula selected from those indicated at (C), and the hydrogen atom(s) on the benzene ring in these structures are optionally substituted.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT 262352-99-8P
(heat- and water-resistant fluorine-containing polybenzoxazoles with low dielec. constant)
RN 262352-99-8 USPATFULL
CN [1,1'-Biphenyl]-4,4'-dicarbonyl dichloride, 2,2'-bis(trifluoromethyl)-, polymer with 4,4'-(1-methylethylidene)bis[2-aminophenol] (9CI) (CA INDEX NAME)

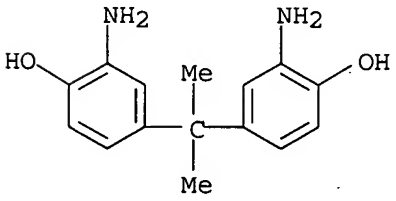
CM 1

CRN 86536-25-6
CMF C16 H6 Cl2 F6 O2



CM 2

CRN 1220-78-6
CMF C15 H18 N2 O2

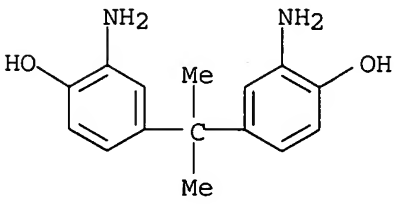


L24 ANSWER 17 OF 24 USPATFULL on STN
AN 2000:151196 USPATFULL

CAS ONLINE PRINTOUT

TI Aiming and focussing device for fiber-transported laser radiation
IN Johnston, Timothy J., Mountain View, CA, United States
Nightingale, John L., Portola Valley, CA, United States
PA Coherent, Inc., Santa Clara, CA, United States (U.S. corporation)
PI US 6144787 20001107
AI US 1998-72483 19980504 (9)
DT Utility
FS Granted
EXNAM Primary Examiner: Bovernick, Rodney; Assistant Examiner: Stahl, Michael J.
LREP Limbach & Limbach L.L.P.
CLMN Number of Claims: 26
ECL Exemplary Claim: 1
DRWN 10 Drawing Figure(s); 6 Drawing Page(s)
LN.CNT 578
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
AB Apparatus (20) for aiming and projecting laser radiation emitted from an output-face (56) at an output-end (52) of an optical-fiber transmitter (54), includes a target (26) surrounding the output-end of the optical-fiber transmitter and held in a fixed relationship therewith. One or more light sources (46) illuminate the target with visible light such that the target directs at least a portion of the visible light in the emission direction of the laser radiation whereby when the optical-fiber transmitter is directed toward a surface, the visible light directed by the target indicates an incidence region of the laser radiation on the surface. The apparatus optionally includes an optical system (27) arranged to project a visible image (72) of the target and an image (74) of the output-face of the optical fiber transmitter. The degree of focus of the visible target-image on the surface corresponds to the degree of focus of the laser radiation on the surface.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT 1220-78-6P
(preparation of mitochondria protecting agents)
RN 1220-78-6 USPATFULL
CN Phenol, 4,4'-(1-methylethylidene)bis[2-amino- (CA INDEX NAME)



L24 ANSWER 18 OF 24 USPATFULL on STN
AN 2000:18546 USPATFULL
TI Photosensitive polyimide
IN Chiang, Lin-Chiu, Kitaibaraki, Japan
Lin, Jeng-Tain, Kitaibaraki, Japan
PA Nippon Mektron, Limited, Tokyo, Japan (non-U.S. corporation)
PI US 6025461 20000215
AI US 1998-129581 19980805 (9)
PRAI JP 1997-279959 19970926
DT Utility
FS Granted
EXNAM Primary Examiner: Hampton-Hightower, P.
LREP Barnes & Thornburg

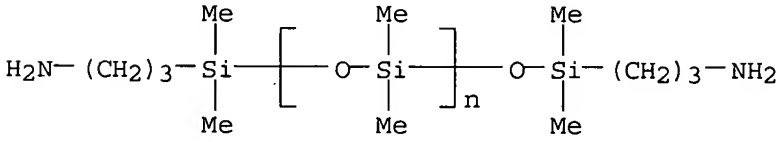
CAS ONLINE PRINTOUT

CLMN Number of Claims: 7
ECL Exemplary Claim: 1
DRWN No Drawings
LN.CNT 247
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
AB A photosensitive polyimide, which comprises a copolymer of (A) three diamine compounds mixture consisting of a diaminopolysiloxane, a hydroxyl group-containing diamine or carboxyl group-containing diamine and 1,4-bis[2-(3-aminobenzoyl)ethenyl]benzene with (B) an aromatic tetrocarboxylic acid dianhydride or a dicarboxylic anhydride having a 2,5-dioxotetrahydrofuryl group as one acid anhydride group, is soluble in all-purpose low boiling organic solvents, typically methyl ethyl ketone and provides a negative type photosensitive polyimide, which is developable with an aqueous alkaline solution.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT 221688-71-7P
(photosensitive polyimides from a diamine blend and a tetracarboxylic acid dianhydride for neg.-type photosensitive use)
RN 221688-71-7 USPATFULL
CN 1,3-Isobenzofurandione, 3a,4,5,7a-tetrahydro-7-methyl-5-(tetrahydro-2,5-dioxo-3-furanyl)-, polymer with α-[(3-aminopropyl)dimethylsilyl]-ω-[[(3-aminopropyl)dimethylsilyl]oxy]poly[oxy(dimethylsilylene)], 4,4'-(1-methylethylidene)bis[2-aminophenol] and 3,3'-(1,4-phenylene)bis[1-(3-aminophenyl)-2-propen-1-one] (9CI) (CA INDEX NAME)

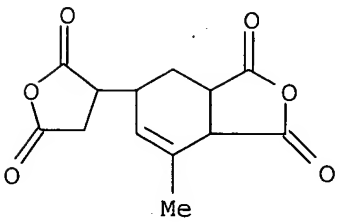
CM 1

CRN 97917-34-5
CMF (C2 H6 O Si)n C10 H28 N2 O Si2
CCI PMS



CM 2

CRN 73003-90-4
CMF C13 H12 O6

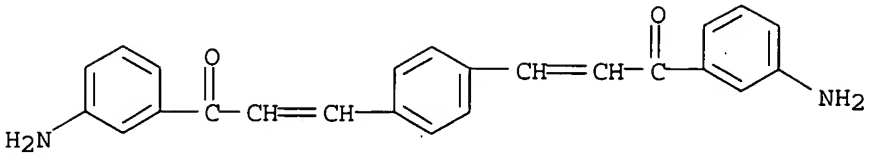


CM 3

CRN 70943-30-5

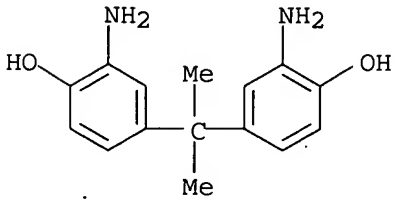
CAS ONLINE PRINTOUT

CMF C24 H20 N2 O2



CM 4

CRN 1220-78-6
CMF C15 H18 N2 O2

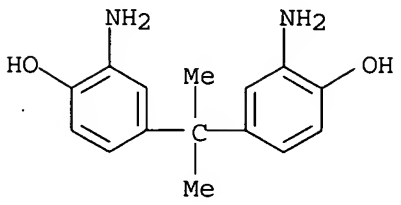


L24 ANSWER 19 OF 24 USPATFULL on STN
AN 1999:108933 USPATFULL
TI Dissipator for reducing electrostatic charge in fines generated by a coffee grinder
IN McNeill, Robert C., Georgetown, IN, United States
Signorello, Richard J., La Grange, KY, United States
PA Grindmaster Corporation, Louisville, KY, United States (U.S. corporation)
PI US 5950941 19990914
AI US 1998-72487 19980504 (9)
DT Utility
FS Granted
EXNAM Primary Examiner: Husar, John M.
LREP Wheat, Smith & Beres, PLC, Smith, Vance A., Nagle, Jr., David W.
CLMN Number of Claims: 18
ECL Exemplary Claim: 14
DRWN 23 Drawing Figure(s); 8 Drawing Page(s)
LN.CNT 458
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
AB An apparatus for the preparation of ground material used to make a beverage includes an electrostatic precipitator to prevent the separation of chaff fines from a main stream of the ground material. The apparatus includes a grinder and a chute leading from an exit opening in the grinder to a receptacle for receiving the ground material. The electrostatic dissipator is positioned near the exit opening for minimizing the electrostatic charge on chaff fines created by the grinder, thereby preventing the separation of chaff fines from the main stream of ground material.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT 1220-78-6P
(preparation of mitochondria protecting agents)
RN 1220-78-6 USPATFULL

CAS ONLINE PRINTOUT

CN Phenol, 4,4'-(1-methylethylidene)bis[2-amino- (CA INDEX NAME)



L24 ANSWER 20 OF 24 USPATFULL on STN
AN 97:120691 USPATFULL
TI Fluorine-containing elastomer composition
IN Yamamoto, Yuichi, Ibaraki, Japan
Tatsu, Haruyoshi, Ibaraki, Japan
Alexeevna, Volkova Margarita, Saint Petersburg, Russian Federation
Vasilyevich, Sokolov Sergey, Saint Petersburg, Russian Federation
Vladimirovich, Veretennikov Nikolai, Saint Petersburg, Russian Federation
PA The Central Synthetic Rubbers Research Institute, Saint Petersburg, Russian Federation (non-U.S. corporation)
Nippon Mektron Limited, Tokyo, Japan (non-U.S. corporation)
PI US 5700879 19971223
AI US 1995-543502 19951016 (8)
PRAI JP 1994-282940 19941021
DT Utility
FS Granted
EXNAM Primary Examiner: Lipman, Bernard
LREP Barnes & Thornburg
CLMN Number of Claims: 3
ECL Exemplary Claim: 1
DRWN No Drawings
LN.CNT 236
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
AB A fluorine-containing elastomer composition, which comprises a terpolymer of tetrafluoroethylene, perfluoro(lower alkyl vinyl ether) and cyano group-containing (perfluorovinylether) represented by the following general formula:

CF.sub.2 .dbd.CF[OCF.sub.2 CF(CF.sub.3)]nCN

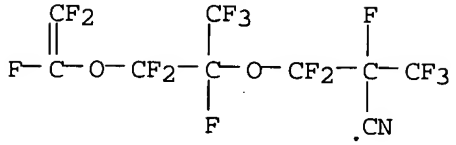
wherein n is an integer of 1 to 5, and a bis(aminophenyl) compound represented by the following general formula as a cross-linking agent: ##STR1## , wherein A is, for example, an alkylidene group, and X and Y are a hydroxyl group or an amino group, can produce vulcanized products having a good heat resistance and good physical properties, and the bis(aminophenyl) compound has no problem as to its safety.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT 178200-07-2P
(fluorine-containing elastomer having cyano crosslinkable groups and vulcanizate with phys. properties and a good compression set)
RN 178200-07-2 USPATFULL
CN Propanenitrile, 2-[[1-[difluoro[(trifluoroethenyl)oxy]methyl]-1,2,2,2-tetrafluoroethoxy]difluoromethyl]-2,3,3,3-tetrafluoro-, polymer with 4,4'-(1-methylethylidene)bis[2-aminophenol], tetrafluoroethene and trifluoro(trifluoromethoxy)ethene (9CI) (CA INDEX NAME)

CAS ONLINE PRINTOUT

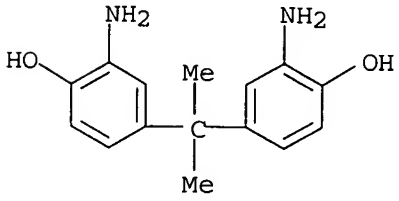
CM 1

CRN 54682-64-3
CMF C9 F15 N O2



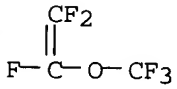
CM 2

CRN 1220-78-6
CMF C15 H18 N2 O2



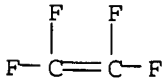
CM 3

CRN 1187-93-5
CMF C3 F6 O



CM 4

CRN 116-14-3
CMF C2 F4



L24 ANSWER 21 OF 24 USPATFULL on STN
AN 92:40552 USPATFULL
TI Photosensitive polyimide compositions
IN Kwong, Ranee W., Wappingers Falls, NY, United States
Sachdev, Harbans S., Wappingers Falls, NY, United States
Sachdev, Krishna G., Wappingers Falls, NY, United States
PA IBM Corporation, Armonk, NY, United States (U.S. corporation)

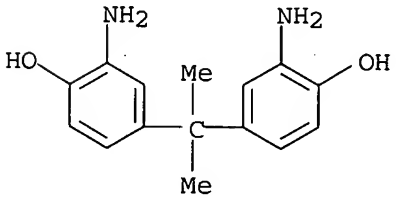
CAS ONLINE PRINTOUT

PI US 5114826 19920519
AI US 1989-458130 19891228 (7)
DT Utility
FS Granted
EXNAM Primary Examiner: Lovering, Richard D.
LREP Stemwedel, John A.
CLMN Number of Claims: 23
ECL Exemplary Claim: 1
DRWN No Drawings
LN.CNT 713
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
AB New photosensitive polyimide compositions and processes of using the same in the fabrication of electronic components are provided. These compositions are comprised of ##STR1## containing polyamic acids and/or the corresponding hydroxy-polyamic esters, or hydroxypolyimides and a photoactive component as an additive or as covalently bonded functionality on the polymer chain. These compositions provide positive or negative patterning options and may be used as conventional resist materials, as imageable dielectric or passivating layers, as high Tg ion implant masks or as imageable lift-off layers in the fabrication of multilevel metal structures.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT 137892-33-2P
(preparation and use of, in photosensitive composition)
RN 137892-33-2 USPATFULL
CN 1,3-Isobenzofurandione, 5,5'-[2,2,2-trifluoro-1-(trifluoromethyl)ethylidene]bis-, polymer with 4,4'-(1-methylethylidene)bis[2-aminophenol] (9CI) (CA INDEX NAME)

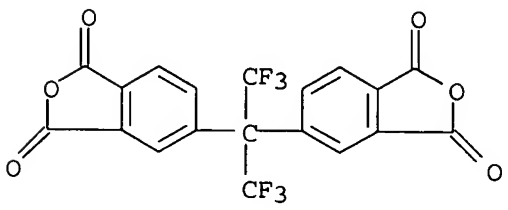
CM 1

CRN 1220-78-6
CMF C15 H18 N2 O2



CM 2

CRN 1107-00-2
CMF C19 H6 F6 O6



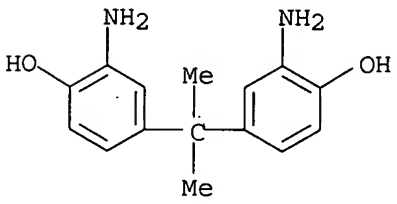
CAS ONLINE PRINTOUT

L24 ANSWER 22 OF 24 USPATFULL on STN
AN 72:31227 USPATFULL
TI RANDOM BENZIMIDAZOLE-BENZOXAZOLE COPOLYMERS AND METHODS OF PREPARATION
IN Loft, John T., Springfield, NJ, United States
Conciatori, Anthony B., Chatham, NJ, United States
Chenevey, Edward C., North Plainfield, NJ, United States
PA Celanese Corporation, New York, NY, United States
PI US 3671491 19720620
AI US 1969-810813 19690326 (4)
DT Utility
FS Granted
EXNAM Primary Examiner: Short, William H.; Assistant Examiner: Lee, L. L.
LREP Morgan; Thomas J., Barris; C. B., Miller; C. E.
CLMN Number of Claims: 12
DRWN No Drawings
LN.CNT 578
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
AB Random copolymers which consist essentially of from about 90 to about 10 percent of recurring benzimidazole structural units and correspondingly from about 10 to about 90 percent of recurring benzoxazole structural units are provided. Several polymerization methods including, for example, a two stage melt-solid state procedure, are described.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT 36864-44-5P
(manufacture of, by melt-solid state polymerization)
RN 36864-44-5 USPATFULL
CN 1,3-Benzenedicarboxylic acid, diphenyl ester, polymer with [1,1'-biphenyl]-3,3',4,4'-tetramine and 4,4'-(1-methylethylidene)bis[2-aminophenol] (9CI) (CA INDEX NAME)

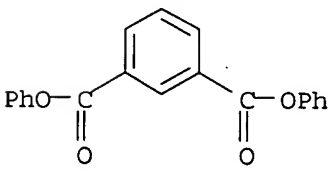
CM 1

CRN 1220-78-6
CMF C15 H18 N2 O2



CM 2

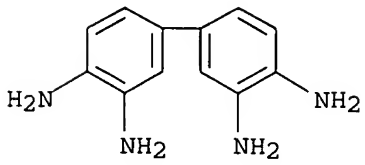
CRN 744-45-6
CMF C20 H14 O4



CAS ONLINE PRINTOUT

CM 3

CRN 91-95-2
CMF C12 H14 N4



L24 ANSWER 23 OF 24 USPATFULL on STN
AN 72:27424 USPATFULL
TI SOLVENT SOLUBLE AROMATIC POLYMIDES AND PRODUCTION THEREOF
IN Suzuki, Munehiko, Yokohama-shi, Japan
Hosokawa, Etsuo, Yokohama-shi, Japan
Waki, Misao, Kawasaki-shi, Japan
Fukushima, Masatada, Yokohama-shi, Japan
PA Shawa Densen Denran Kabushiki Kaisha a/k/a Showa Electric Wire & Cable Co., Ltd., Kanagawa-ken, Japan
PI US 3666709 19720530
AI US 1969-885140 19691215 (4)
PRAI JP 1968-91760 19681214
DT Utility
FS Granted
EXNAM Primary Examiner: Liebman, Morris; Assistant Examiner: Zahlen, Richard
LREP Holman & Stern
CLMN Number of Claims: 31
DRWN 9 Drawing Figure(s); 3 Drawing Page(s)
LN.CNT 807
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
AB An aromatic tetracarboxylic acid which is representable by the general formula

and contains at least 30 mol percent of

and a diamine which is representable by the general formula H.sub.2 N--R'--NH.sub.2 and contains at least 30 mol percent of diamines representable by any of ##SPC1##

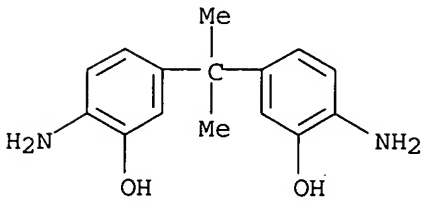
Are heated and caused to react in substantially equal mol quantities in a phenolic solvent or in an aprotic organic polar solvent thereby to produce a new linear aromatic polyimide which is soluble in organic solvents and has high stability for preservation in the form of solutions such as varnishes. This method does not require a step of thoroughly dehydrating the aromatic tetracarbosylic acid component prior to the reaction.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT 28452-01-9P
(manufacture of, for coatings)
RN 28452-01-9 USPATFULL
CN Phthalic anhydride, 4,4'-carbonyldi-, polymer with benzidine and 3,3'-isopropylidenebis[6-aminophenol] (8CI) (CA INDEX NAME)

CM 1

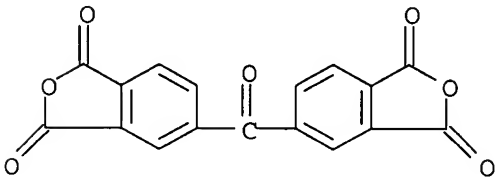
CAS ONLINE PRINTOUT

CRN 22445-96-1
CMF C15 H18 N2 O2



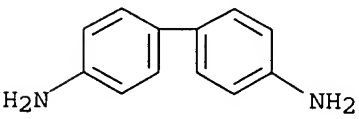
CM 2

CRN 2421-28-5
CMF C17 H6 O7



CM 3

CRN 92-87-5
CMF C12 H12 N2



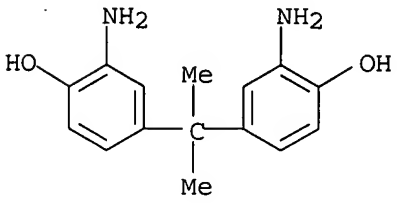
L24 ANSWER 24 OF 24 USPATFULL on STN
AN 71:44916 USPATFULL
TI LOW-TEMPERATURE PROCESS FOR THE PRODUCTION OF POLYAMIDES
IN Steinmann, Henry W., Sparta, NJ, United States
Pollard, Edward T., Middlesex, NJ, United States
PA Celanese Corporation, New York, NY, United States
PI US 3624033 19711130
AI US 1969-840248 19690709 (4)
DT Utility
FS Granted
EXNAM Primary Examiner: Short, William H.; Assistant Examiner: Lee, L. L.
LREP Morgan; Thomas J., Barris; C. B., Miller; C. E.
CLMN Number of Claims: 6
DRWN 1 Drawing Figure(s); 1 Drawing Page(s)
LN.CNT 642
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
AB Polyamides are rapidly produced at relatively low temperatures (e.g., ambient temperatures) by polymerization reaction of diamines with diacyl

halides. An aqueous solution of a diammonium salt (e.g., a diamine dihydrohalide) and a solution of an equivalent amount of a diacyl halide (e.g., a diacyl chloride) in a water-immiscible solvent (e.g., methylene chloride) are intimately mixed at medium to high shear rate followed by the rapid addition, with continued agitation, of an aqueous solution of an amount of an acid-acceptor e.g., an alkali metal monocarboxylate) sufficient to liberate the diamine and neutralize the byproduct hydrogen halide.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.
IT 29186-76-3P 29791-93-3P
(preparation of, low temperature, properties of)
RN 29186-76-3 USPATFULL
CN 1,3-Benzenedicarbonyl dichloride, polymer with 4,4'-(1-methylethylidene)bis[2-aminophenol] (9CI) (CA INDEX NAME)

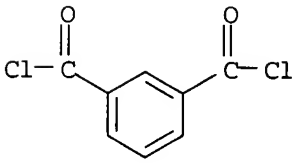
CM 1

CRN 1220-78-6
CMF C15 H18 N2 O2



CM 2

CRN 99-63-8
CMF C8 H4 Cl2 O2

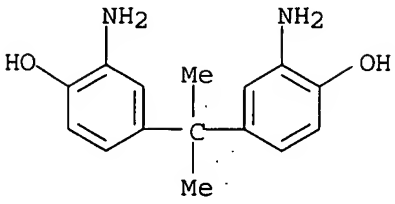


RN 29791-93-3 USPATFULL
CN 1,4-Benzenedicarbonyl dichloride, polymer with 4,4'-(1-methylethylidene)bis[2-aminophenol] (9CI) (CA INDEX NAME)

CM 1

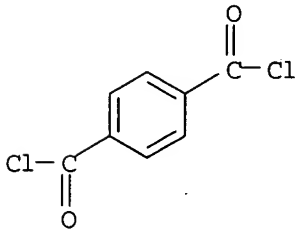
CRN 1220-78-6
CMF C15 H18 N2 O2

CAS ONLINE PRINTOUT



CM 2

CRN 100-20-9
CMF C8 H4 Cl2 O2



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